

Notice of References Cited	Application/Control No. 10/790,457	Applicant(s)/Patent Under Reexamination PAWLOSKI ET AL.	
	Examiner Caleen O. Sullivan	Art Unit 1756	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,024,801	02-2000	Wallace et al.	134/1
*	B	US-6,612,317	09-2003	Costantini et al.	134/58R
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Switkes et al.; "Immersion Lithography at 157nm", J. Vac. Sci. Technol. B 19(6), Nov.Dec. 2001; pp. 2353-2356.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.